

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	7076	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) and (((electron adj beam) or (e adj beam) or evaporat\$6 or vaporiz\$8) with (Hf or hafnium or HfO2 or HfO or "HfO.sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf. sub.2 O.sub.3")) and (("no" or "not" or "without") near4 (heat\$4 or ion or bombard\$7 or energy))	US-PGPUB; USPAT	OR	ON	2005/03/29 13:37
L2	79	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or stack or mirror) and (((electron adj beam) or (e adj beam) or evaporat\$6 or vaporiz\$8) with (Hf or hafnium or HfO2 or HfO or "HfO.sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf. sub.2 O.sub.3")) and (("no" or "not" or "without") near4 (heat\$4 or ion or bombard\$7 or energy) with (substrate or base or workpiece or mirror or coat\$4))	US-PGPUB; USPAT	OR	ON	2005/03/29 13:45
L3	79	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or stack or mirror) and (((electron adj beam) or (e adj beam) or evaporat\$6 or vaporiz\$8) with (Hf or hafnium or HfO2 or HfO or "HfO.sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf. sub.2 O.sub.3")) and (("no" or "not" or "without") near4 (heat\$4 or ion or bombard\$7 or energy) with (substrate or base or workpiece or mirror or coat\$4))	US-PGPUB; USPAT	OR	ON	2005/03/29 13:49

L4	2	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or stack or mirror)) and (((electron adj beam) or (e adj beam) or evaporat\$6 or vaporiz\$8) with (Hf or hafnium or HfO2 or HfO or "HfO.sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3")) and ("no" or "not" or "without") near4 (heat\$4 or ion or bombard\$7 or energy) with (substrate or base or workpiece or mirror or coat\$4))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/29 13:47
L5	610	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or stack or mirror)) and (((electron adj beam) or (e adj beam) or evaporat\$6 or vaporiz\$8) with (Hf or hafnium or HfO2 or HfO or "HfO.sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3")) and (temperature with (substrate or base or workpiece or mirror or coat\$4)))	US-PGPUB; USPAT	OR	ON	2005/03/29 13:49
L6	211	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or stack or mirror)) and (((electron adj beam) or (e adj beam) or evaporat\$6 or vaporiz\$8) with (Hf or hafnium or HfO2 or HfO or "HfO.sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3")) same (temperature with (substrate or base or workpiece or mirror or coat\$4)))	US-PGPUB; USPAT	OR	ON	2005/03/29 14:03
L7	0	(hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3") and "5726919".pn.	US-PGPUB; USPAT	OR	ON	2005/03/29 13:57

L8	16	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or stack or mirror)) and (((electron adj beam) or (e adj beam) or evaporat\$6 or vaporiz\$8) with (Hf or hafnium or HfO2 or HfO or "HfO.sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3")) same (temperature with (substrate or base or workpiece or mirror or coat\$4)))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/29 14:05
L9	1	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or stack or mirror) with density with (determin\$9 or optimiz\$9 or optimal\$8 or based or depend\$7))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/29 14:06
L10	21	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or stack or mirror) with density with (determin\$9 or optimiz\$9 or optimal\$8 or based or depend\$7))	US-PGPUB; USPAT	OR	ON	2005/03/29 14:09
L11	149	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or stack or mirror) with density)	US-PGPUB; USPAT	OR	ON	2005/03/29 14:21
L12	128	L11 not L10	US-PGPUB; USPAT	OR	ON	2005/03/29 14:14
L13	0	"5618575".pn. and (hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO.sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3")	US-PGPUB; USPAT	OR	ON	2005/03/29 14:14
L14	14	(electron adj beam) same (density near3 (depend\$6 or based or determin\$9) with temperature)	US-PGPUB; USPAT	OR	ON	2005/03/29 14:25
L15	11	(electron adj beam) same (density with temperature with oxide)	US-PGPUB; USPAT	OR	ON	2005/03/29 14:23

L16	3	("427"/\$).ccls. and (density near3 (depend\$6 or based or determin\$9) with temperature with oxide)	US-PGPUB; USPAT	OR	ON	2005/03/29 14:26
L17	138	("427"/\$).ccls. and (density near3 (depend\$6 or based or determin\$9) with temperature)	US-PGPUB; USPAT	OR	ON	2005/03/29 14:28
L18	223	(density with (oxide or coat\$4 or film or layer) with (depend\$6 or based or determin\$9 or function) with temperature with substrate)	US-PGPUB; USPAT	OR	ON	2005/03/29 14:36
L19	42	L18 and (electron adj beam)	US-PGPUB; USPAT	OR	ON	2005/03/29 14:29
L20	29	(porosity with (oxide or coat\$4 or film or layer) with (depend\$6 or based or determin\$9 or function) with temperature with substrate)	US-PGPUB; USPAT	OR	ON	2005/03/29 14:38
L21	195	(porosity with (oxide or coat\$4 or film or layer) with temperature with substrate)	US-PGPUB; USPAT	OR	ON	2005/03/29 14:38
L22	28	L21 and (electron adj beam)	US-PGPUB; USPAT	OR	ON	2005/03/29 14:38
S1	1	"5733042".pn.	US-PGPUB; USPAT	OR	ON	2005/03/28 15:06
S2	161	(Bernard.in. or Dijon.in. or Rafin.in.) and (hafnia or (hafnium adj \$3oxide) or HfO2 or HfO or "HfO. sub.2")	US-PGPUB; USPAT	OR	ON	2005/03/28 15:20
S3	7	(Bernard.in. or Dijon.in. or Rafin.in.) and ((hafnia or (hafnium adj \$3oxide) or HfO2 or HfO or "HfO. sub.2") with (amorphous or noncrystal\$6 or (non adj crystal\$7) or void or pore or porous or porus or density))	US-PGPUB; USPAT	OR	ON	2005/03/28 15:09
S4	2	(Bernard.in. or Dijon.in. or Rafin.in.) and ((hafnia or (hafnium adj \$3oxide) or HfO2 or HfO or "HfO. sub.2") with (amorphous or noncrystal\$6 or (non adj crystal\$7) or void or pore or porous or porus or density))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/28 15:10
S5	2	(Bernard.in. or Dijon.in. or Rafin.in.) and ((hafnia or (hafnium adj \$3oxide) or HfO2 or HfO or "HfO. sub.2") same (vacuum or evaporat\$6 or (electron adj (beam or gun))))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/28 15:12

S6	8	(Bernard.in. or Dijon.in. or Rafin.in.) and ((hafnia or (hafnium adj \$3oxide) or HfO2 or HfO or "HfO. sub.2") same (vacuum or evaporat\$6 or (electron adj (beam or gun))))	US-PGPUB; USPAT	OR	ON	2005/03/28 15:12
S7	10	(Bernard.in. or Dijon.in. or Rafin.in.) and ((hafnia or (hafnium adj \$3oxide) or HfO2 or HfO or "HfO. sub.2") same (cold or (room adj temperature) or cool\$4))	US-PGPUB; USPAT	OR	ON	2005/03/28 15:14
S8	0	(Bernard.in. or Dijon.in. or Rafin.in.) and ((hafnia or (hafnium adj \$3oxide) or HfO2 or HfO or "HfO. sub.2") same (cold or (room adj temperature) or cool\$4))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/28 15:30
S9	1	(Bernard.in. or Dijon.in. or Rafin.in.) and ((hafnia or (hafnium adj \$3oxide) or HfO2 or HfO or "HfO. sub.2") same ("without" near3 (energy or ion or plasma or heat\$4)))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/28 15:31
S10	1	(Bernard.in. or Dijon.in. or Rafin.in.) and ((hafnia or (hafnium adj \$3oxide) or HfO2 or HfO or "HfO. sub.2") same ("without" near3 (energy or ion or plasma or heat\$4)))	US-PGPUB; USPAT	OR	ON	2005/03/28 15:16
S11	142	S2 not (S3 or S4 or S6 or S7 or S10)	US-PGPUB; USPAT	OR	ON	2005/03/28 15:16
S12	34	(Bernard.in. or Dijon.in. or Rafin.in.) and (hafnia or (hafnium adj \$3oxide) or HfO2 or HfO or "HfO. sub.2")	USOCR	OR	ON	2005/03/28 15:19
S13	2336	(427/162,164,166).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/03/28 15:19
S14	1351	(427/255.23,255.31,255.7).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/03/28 15:19
S15	1098	(427/294).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/03/28 15:19
S16	466	(427/419.3).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/03/28 15:19
S17	1546	(359/584,588,589,838).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/03/28 15:19
S18	6378	S13 S14 S15 S16 S17	US-PGPUB; USPAT	OR	ON	2005/03/29 10:07

S19	7	S18 and ((hafnia or (hafnium adj \$3oxide) or HfO2 or HfO or "HfO. sub.2") with (pore or porous or porus or porosity or void or amorphous or amorphus or noncrystal\$6 or (non adj crystal\$5)) with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6))	US-PGPUB; USPAT	OR	ON	2005/03/28 15:22
S20	8	S18 and ((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO.sub.2") with (pore or porous or porus or porosity or void or amorphous or amorphus or noncrystal\$6 or (non adj crystal\$5)) with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6))	US-PGPUB; USPAT	OR	ON	2005/03/28 15:22
S21	8	S18 and ((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO.sub.2") with (pore or porous or porus or porosity or void or amorphous or amorphus or noncrystal\$6 or (non adj crystal\$5)) with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror))	US-PGPUB; USPAT	OR	ON	2005/03/28 15:25
S22	10	S18 and ((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO.sub.2") with (pore or porous or porus or porosity or void or amorphous or amorphus or noncrystal\$6 or (non adj crystal\$5) or density) with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror))	US-PGPUB; USPAT	OR	ON	2005/03/28 15:26
S23	601	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO. sub.2") with (pore or porous or porus or porosity or void or amorphous or amorphus or noncrystal\$6 or (non adj crystal\$5) or density) with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror))	US-PGPUB; USPAT	OR	ON	2005/03/28 15:37
S24	180	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO. sub.2") with (pore or porous or porus or porosity or void or amorphous or amorphus or noncrystal\$6 or (non adj crystal\$5) or density) with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/28 15:27

S25	8	S24 and ((vacuum near3 (deposit\$5 or evaporat\$5 or vapor\$9)) or (electron adj beam) or (react\$5 near3 evaporat\$5))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/28 15:39
S26	13	S24 and (cold or (room adj temperature) or cool\$4)	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/28 15:41
S27	2	S24 and ("without" near3 (energy or ion or plasma or heat\$4))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/28 15:43
S28	159	S24 not (S25 or S26 or S27)	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/28 15:32
S29	601	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3") with (pore or porous or porus or porosity or void or amorphous or amorphus or noncrystal\$6 or (non adj crystal\$5) or density) with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror))	US-PGPUB; USPAT	OR	ON	2005/03/28 16:05
S30	0	S29 same ((vacuum near3 (deposit\$5 or evaporat\$5 or vapor\$9)) or (electron adj beam) or (react\$5 near3 evaporat\$5))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/28 15:39
S31	21	S29 same ((vacuum near3 (deposit\$5 or evaporat\$5 or vapor\$9)) or (electron adj beam) or (react\$5 near3 evaporat\$5))	US-PGPUB; USPAT	OR	ON	2005/03/28 15:39
S32	17	S29 same (cold or (room adj temperature) or cool\$4)	US-PGPUB; USPAT	OR	ON	2005/03/28 15:42
S33	1	S29 same ("without" near3 (energy or ion or plasma or heat\$4))	US-PGPUB; USPAT	OR	ON	2005/03/28 15:43
S34	12	S29 and ((protect\$5 or damag\$5) with laser)	US-PGPUB; USPAT	OR	ON	2005/03/28 15:44
S35	288	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) same (cool\$3 or cold or (room adj temperature)))	US-PGPUB; USPAT	OR	ON	2005/03/28 15:49
S36	7	S35 and S18	US-PGPUB; USPAT	OR	ON	2005/03/28 15:48

S37	1	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) same ((reactive adj evaporat\$5) with (Hf or hafnium) with (O2 or oxygen or "O.sub.2")))	US-PGPUB; USPAT	OR	ON	2005/03/28 16:00
S38	25	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) same ((evaporat\$5) with (Hf or hafnium) with (O2 or oxygen or "O.sub.2")))	US-PGPUB; USPAT	OR	ON	2005/03/28 16:24
S39	9	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) same ((evaporat\$5) with (Hf or hafnium) with (O2 or oxygen or "O.sub.2")))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/28 16:03
S40	56	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3") near3 (amorphous or amorphus) with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror))	US-PGPUB; USPAT	OR	ON	2005/03/28 16:19
S41	56	S40 and S29	US-PGPUB; USPAT	OR	ON	2005/03/28 16:07
S42	28	S40 and (substrate with temperature)	US-PGPUB; USPAT	OR	ON	2005/03/28 16:09
S43	28	S40 not S42	US-PGPUB; USPAT	OR	ON	2005/03/28 16:09
S44	16	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3") near3 (amorphous or amorphus) with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/29 10:08

S45	318	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3") with (silica or SiO2 or "SiO.sub.2" or SiO or (silicon adj \$3oxide)) with (mirror or multilayer or (multi adj layer) or stack or reflect\$6))	US-PGPUB; USPAT	OR	ON	2005/03/28 16:20
S46	356	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3") with (silica or SiO2 or "SiO.sub.2" or SiO or (silicon adj \$3oxide)) with (mirror or multilayer or (multi adj layer) or stack or reflect\$6 or (alternat\$6 near2 layer)))	US-PGPUB; USPAT	OR	ON	2005/03/28 16:21
S47	22	S46 and S18	US-PGPUB; USPAT	OR	ON	2005/03/28 16:21
S48	17	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) and ((evaporat\$5) with (Hf or hafnium) same (O2 or oxygen or "O.sub.2")))) and (temperature near2 room)	US-PGPUB; USPAT	OR	ON	2005/03/28 16:29
S49	24	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) and ((evaporat\$5) with (Hf or hafnium) same (O2 or oxygen or "O.sub.2")))) and (temperature with substrate)	US-PGPUB; USPAT	OR	ON	2005/03/28 16:29
S50	2	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) and ((evaporat\$5) with (Hf or hafnium) same (O2 or oxygen or "O.sub.2")))) and (temperature with substrate)	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/28 16:28

S51	0	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) and ((evaporat\$5) with (Hf or hafnium) same (O2 or oxygen or "O.sub.2")))) and (temperature near2 room)	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/28 16:29
S52	19	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) and ((evaporat\$5) with (Hf or hafnium) same (O2 or oxygen or "O.sub.2")))) same (temperature))	US-PGPUB; USPAT	OR	ON	2005/03/28 16:30
S53	1702	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) same temperature)	US-PGPUB; USPAT	OR	ON	2005/03/28 16:33
S54	309	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO. sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) same temperature)	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/28 16:31
S55	40	S53 and S18	US-PGPUB; USPAT	OR	ON	2005/03/28 16:33
S56	2336	(427/162,164,166).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/03/29 10:07
S57	1353	(427/255.23,255.31,255.7).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/03/29 10:07
S58	1098	(427/294).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/03/29 10:07
S59	466	(427/419.3).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/03/29 10:07
S60	1547	(359/584,588,589,838).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/03/29 10:07
S61	6381	S56 S57 S58 S59 S60	US-PGPUB; USPAT	OR	ON	2005/03/29 10:07

S62	18	S61 and ((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO.sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror)).ti,ab.	US-PGPUB; USPAT	OR	ON	2005/03/29 10:12
S63	479	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO.sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) same (amorphous or amorphus))	US-PGPUB; USPAT	OR	ON	2005/03/29 10:44
S64	95	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO.sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) same (amorphous or amorphus))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/29 10:13
S65	38	S63 and (((electron adj. beam) or (e adj beam) or evaporat\$6 or vaporiz\$8) with (Hf of hafnium))	US-PGPUB; USPAT	OR	ON	2005/03/29 10:23
S66	8	S63 and S61	US-PGPUB; USPAT	OR	ON	2005/03/29 10:24
S67	437	S63 not (S65, or S66)	US-PGPUB; USPAT	OR	ON	2005/03/29 10:24
S68	12	((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO.sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror) same (amorphous or amorphus))	USOCR	OR	ON	2005/03/29 10:47
S69	17	("427"/\$).ccls. and ((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO.sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf.sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror)) and (((electron adj beam) or (e adj beam) or evaporat\$6 or vaporiz\$8) with (Hf of hafnium))	USOCR	OR	ON	2005/03/29 10:48

S70	75	("427"/\$).ccls. and ((hafnia or ((hafnium or Hf) near4 \$3oxide) or HfO2 or HfO or "HfO.sub.2" or Hf2O3 or "Hf.sub.2O.sub.3" or "Hf. sub.2 O.sub.3") with (deposit\$4 or coat\$4 or film or \$5layer or evaporat\$6 or stack or mirror)) and (((electron adj beam) or (e adj beam) or evaporat\$6 or vaporiz\$8) with (Hf or hafnium))	US-PGPUB; USPAT	OR	ON	2005/03/29 13:33
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